

REMARKS

These amendments and remarks are being filed in response to the Office Action dated March 22, 2006. For the following reasons this application should be allowed and the case passed to issue. No new matter is introduced by this amendment. The amendment to claim 1 is supported by claim 4. Claims 3, 5, 6, 7, and 12 are amended to maintain proper dependency.

Claims 1, 3, and 5-20 are pending in this application. Claims 1-3 and 16 are rejected. Claims 4-15 are objected to. Claims 17-20 are allowed. Claims 1, 3, 5, 6, 7, and 12 have been amended in this response. Claims 2 and 4 have been canceled in this response.

Allowable Subject Matter

Claims 17-20 are allowed.

Claim 4 is objected to but would be allowable if rewritten in independent form.

Applicants gratefully acknowledge the indication of allowable subject matter. The limitations of claim 4 have been added to amended claim 1. Therefore, claim 1 should be allowable for at least the same reasons as claim 4.

Claim Rejections Under 35 U.S.C. § 103

Claims 1-3 and 16 were rejected under 35 U.S.C. § 103(a) as being unpatentable over Jeans (U.S. Pat. No. 6,808,646) alone, or in view of Nakayama et al. (U.S. Pat. No. 5,112,025). This rejection is traversed, and reconsideration and withdrawal thereof respectfully requested.

The Examiner indicated that claim 4 would be allowable if rewritten in independent form. Claim 1 has been amended to include the limitations of claim 4. Therefore, Applicants submit claim 1 is allowable, as the cited prior art does not suggest a method of manufacturing a stamper/imprinter for use in patterning of a recording medium, comprising sequential steps of:

(a) providing a substrate/workpiece comprising a topographically patterned surface including a plurality of projections and depressions corresponding to a pattern to be formed in a surface of the recording medium, wherein at least the topographically patterned surface is comprised of at least one magnetic material having a high saturation magnetization $B_{\text{sat}} \geq 0.5$ Tesla and a high permeability $\mu \geq \sim 5$; (b) forming a thin release layer in conformal contact with the topographically patterned surface by means of a dry process, wherein the thin release layer is formed of at least one passivating oxide of the at least one magnetic material; (c) forming a thicker layer of a material in conformal contact with the thin release layer on the topographically patterned surface, wherein the thicker layer is formed of at least one magnetic material having a high saturation magnetization $B_{\text{sat}} \geq 0.5$ Tesla and a high permeability $\mu \geq \sim 5$ as the thicker layer; and (d) separating the thicker layer of material from the topographically patterned surface to form therefrom a stamper/imprinter including an imprinting surface having a negative image replica of the topographically patterned surface, separation of the thicker layer of material from the topographically patterned surface being facilitated by the thin release layer formed by the dry process.

Claims 3 and 16 depend from claim 1 and are allowable for at least the same reasons as claim 1.

In view of the above amendments and remarks, Applicants submit that this application should be allowed and the case passed to issue. If there are any questions regarding this Amendment or the application in general, a telephone call to the undersigned would be appreciated to expedite the prosecution of the application.


To the extent necessary, a petition for an extension of time under 37 C.F.R. §1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper,

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including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

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